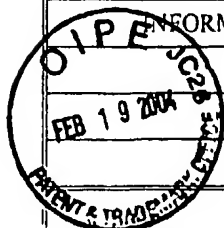


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INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicants			
(Use several sheets if necessary)				Lairson et al.			
				Filing Date		Group	
				12/5/03		Unknown	
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							Yes No
<i>PR</i>	AL	0 547 820	6/1993	EP			
<i>PR</i>	AM	62-183022	8/1987	Japan			
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<i>PR</i>	AS	Sanders, et al., "Coating Technology Based on the Vacuum Arc—A Review", IEEE Transactions on Plasma Science, Vol. 18, No. 6, December 1990, pp. 883-894					
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Foreign Patent Documents							
							Translation
		Document	Date	Country	Class	Subclass	Yes No
<i>PR</i>	AL	11-39647	2/1999	Japan			
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